

Alessandro Giussani

List of Publications by Year in descending order

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docs citations

67

times ranked

1431

citing authors

#	ARTICLE	IF	CITATIONS
1	Evolution of nanodiamond seeds during the chemical vapor deposition of diamond on silicon substrates in oxygen-rich plasmas. <i>Applied Surface Science</i> , 2022, 581, 152103.	6.1	10
2	Characterisation of optical phonons within epitaxial Ge ₂ Sb ₂ Te ₅ /InAs(111) structures. <i>Solid State Communications</i> , 2022, 351, 114788.	1.9	1
3	Block copolymer-“nanodiamond coassembly in solution: towards multifunctional hybrid materials. <i>Nanoscale</i> , 2021, 13, 1639-1651.	5.6	4
4	Boundary curvature effect on the wrinkling of thin suspended films. <i>Applied Physics Letters</i> , 2020, 116, .	3.3	8
5	Nanocrystalline diamond-glass platform for the development of three-dimensional micro- and nanodevices. <i>Diamond and Related Materials</i> , 2019, 98, 107511.	3.9	12
6	Orientations of Al ₄ C ₃ and Al films grown on GaAs substrates. <i>Materials Science in Semiconductor Processing</i> , 2019, 98, 49-54.	4.0	1
7	Self-Assembled InAsP and InAlAs Nanowires on Graphene Via Pseudo-Van Der Waals Epitaxy., 2018, .	0	
8	Exploring the subsurface atomic structure of the epitaxially grown phase-change material $\text{Ge}_{2-\text{Sb}_{2-\text{Te}_5}}$. <i>Physical Review B</i> , 2017, 96, .	3.2	10
9	Integration of thin Al films on In _{0.18} Ga _{0.82} As metamorphic grade structures for low-cost III-V photovoltaics., 2017, .	0	
10	Crystallinity Control in Low-Temperature Growth of Poly-Crystalline Ge by Ion Beam Deposition., 2017, .	0	
11	Development of GaSb solar cells on GaAs by MOVPE via interface misfit technique., 2017, .	1	
12	Development of Aluminum Epilayers as Buffers for GaInAs., 2017, .	0	
13	Giant Rashba- σ Type Spin Splitting in Ferroelectric GeTe(111). <i>Advanced Materials</i> , 2016, 28, 560-565.	21.0	155
14	Metal - Insulator Transition Driven by Vacancy Ordering in GeSbTe Phase Change Materials. <i>Scientific Reports</i> , 2016, 6, 23843.	3.3	93
15	Sub-nanometre resolution of atomic motion during electronic excitation in phase-change materials. <i>Scientific Reports</i> , 2016, 6, 20633.	3.3	29
16	High Yield Fabrication of SPSL-Based DUVLEDs on 6-inch Sapphire Substrates., 2016, .	0	
17	Laser-driven switching dynamics in phase change materials investigated by time-resolved X-ray absorption spectroscopy. <i>Phase Transitions</i> , 2015, 88, 82-89.	1.3	3
18	Local structure of epitaxial GeTe and Ge ₂ Sb ₂ Te ₅ films grown on InAs and Si substrates with (100) and (111) orientations: An x-ray absorption near-edge structure study. <i>Journal of Applied Physics</i> , 2015, 117, 125308.	2.5	9

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19	Picosecond strain dynamics in $\text{Ge}_{x}\text{Sb}_{y}\text{Te}_{z}$ by time-resolved x-ray diffraction. Physical Review B, 2014, 90, .		
20	Toward Truly Single Crystalline GeTe Films: The Relevance of the Substrate Surface. Journal of Physical Chemistry C, 2014, 118, 29724-29730.	3.1	61
21	Structural change upon annealing of amorphous GeSbTe grown on Si(111). Journal of Applied Physics, 2014, 116, .	2.5	35
22	Multiple state transport deduced by weak antilocalization and electron-electron interaction effects in SbxTe_{1-x} layers. Journal of Physics Condensed Matter, 2014, 26, 095802.	1.8	3
23	Ferroelectric switching in epitaxial GeTe films. APL Materials, 2014, 2, .	5.1	67
24	Surface Reconstruction-Induced Coincidence Lattice Formation Between Two-Dimensionally Bonded Materials and a Three-Dimensionally Bonded Substrate. Nano Letters, 2014, 14, 3534-3538.	9.1	70
25	Mirror-symmetric Magneto-optical Kerr Rotation using Visible Light in $[(\text{GeTe})_2(\text{Sb}_2\text{Te}_3)]_n$ Topological Superlattices. Scientific Reports, 2014, 4, 5727.	3.3	57
26	A Density Function Investigation of Excited-State Effects due to Ultrafast Excitation in $\text{Ge}_{2}\text{Sb}_{2}\text{Te}_{5}$ Epitaxial Films. , 2014, , .		0
27	Ultra-fast Processes in Optically Excited $\text{Ge}_{2}\text{Sb}_{2}\text{Te}_{5}$ by Transient X-ray Diffraction Using a Free-Electron Laser. , 2014, , .		0
28	Evidence for topological band inversion of the phase change material $\text{Ge}_2\text{Sb}_2\text{Te}_5$. Applied Physics Letters, 2013, 103, .	3.3	28
29	Transport properties in a Sb-Te binary topological-insulator system. Journal of Physics Condensed Matter, 2013, 25, 345801. Stacking behavior of twin-free type- C oriented CeO_{2} films on hexagonal PrO_{2} layers as seen from the weak antilocalization effect.	1.8	18
30	Recrystallization of an amorphized epitaxial phase-change alloy: A phoenix arising from the ashes. Applied Physics Letters, 2012, 101, 061903.	3.2	12
31	Epitaxial phase-change materials. Physica Status Solidi - Rapid Research Letters, 2012, 6, 415-417. Robust topological surface states in Sb. Physical Review B, 2012, 86, 115111. On the epitaxy of germanium telluride thin films on silicon substrates. Physica Status Solidi (B): Basic Research, 2012, 249, 1939-1944.	2.4	29
32	Crystalline GeTe-based phase-change alloys: Disorder in order. Physical Review B, 2012, 86, .	3.2	28
33	Insight into the Growth and Control of Single-Crystal Layers of $\text{Ge}_{x}\text{Sb}_{y}\text{Te}_z$ Phase-Change Material. Crystal Growth and Design, 2011, 11, 4606-4610.	3.0	34

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37	Complex interface and growth analysis of single crystalline epi- $\text{Si}(111)/\text{Y}_{2}\text{O}_{3}/\text{Pr}_{2}\text{O}_{3}$ /Si(111) heterostructures: Strain engineering by oxide buffer control. <i>Surface and Interface Analysis</i> , 2011, 43, 827-835.	1.8	7
38	Post-deposition annealing of praseodymia films on Si(111) at low temperatures. <i>Journal of Physics Condensed Matter</i> , 2011, 23, 115904.	1.8	1
39	Laboratory-based characterization of heteroepitaxial structures: Advanced experiments not needing synchrotron radiation. <i>Powder Diffraction</i> , 2010, 25, 92-98.	0.2	3
40	Integration of strained and relaxed silicon thin films on silicon wafers via engineered oxide heterostructures: Experiment and theory. <i>Journal of Applied Physics</i> , 2010, 108, .	2.5	6
41	Single crystalline $\text{Pr}_{2-x}\text{Y}_x\text{O}_3$ ($x=0.2$) dielectrics on Si with tailored electronic and crystallographic structure. <i>Journal of Applied Physics</i> , 2010, 108, .	2.5	6
42	Single crystalline $\text{Sc}_{2}\text{O}_3/\text{Y}_{2}\text{O}_3$ heterostructures as novel engineered buffer approach for GaN integration on Si (111). <i>Journal of Applied Physics</i> , 2010, 108, 063502.	2.5	30
43	A novel engineered oxide buffer approach for fully lattice-matched SOI heterostructures. <i>New Journal of Physics</i> , 2010, 12, 093005.	2.9	14
44	Defect structure of Ge(111)/cubic $\text{Pr}_{2}\text{O}_3(111)/\text{Si}(111)$ heterostructures: Thickness and annealing dependence. <i>Journal of Applied Physics</i> , 2009, 106, 073502.	2.5	19
45	Characterization of Semiconductor Films Epitaxially Grown on Thin Metal Oxide Buffer Layers. <i>Solid State Phenomena</i> , 2009, 156-158, 467-472.	0.3	7
46	Heteroepitaxial Integration of Single Crystalline Ge(111) layers on Si(111) via $\text{PrO}_2(111)$ Heterostructures. <i>ECS Transactions</i> , 2009, 16, 287-291.	0.5	0
47	Structure and defects of epitaxial Si(111) layers on $\text{Y}_{2}\text{O}_{3}(111)/\text{Si}(111)$ support systems. <i>Journal of Vacuum Science & Technology B</i> , 2009, 27, 305.	1.3	11
48	Postdeposition annealing induced transition from hexagonal Pr_{2}O_3 to cubic PrO_2 films on Si(111). <i>Journal of Applied Physics</i> , 2009, 105, .	2.5	18
49	Synchrotron x-ray characterization of structural defects in epi-Ge/ $\text{Pr}_{2}\text{O}_{3}/\text{Si}(111)$ layer stacks. <i>Journal Physics D: Applied Physics</i> , 2009, 42, 215411.	6	
50	X-ray characterization of epi-Ge/ $\text{Pr}_{2}\text{O}_{3}/\text{Si}(111)$ layer stacks by pole figures and reciprocal space mapping. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2009, 206, 1809-1815.	1.8	6
51	Engineered Si wafers: On the role of oxide heterostructures as buffers for the integration of alternative semiconductors. <i>Physica Status Solidi C: Current Topics in Solid State Physics</i> , 2009, 6, 653-662.	0.8	31
52	Ge integration on Si via rare earth oxide buffers: From MBE to CVD (Invited Paper). <i>Microelectronic Engineering</i> , 2009, 86, 1615-1620.	2.4	13
53	Atomically smooth and single crystalline Ge(111)/cubic- $\text{Pr}_{2}\text{O}_3(111)/\text{Si}(111)$ heterostructures: Structural and chemical composition study. <i>Journal of Applied Physics</i> , 2009, 105, 033512.	2.5	34
54	Chemical, energetic, and geometric heterogeneity of device-quality (100) surfaces of single crystalline silicon after HFaq etching. <i>Applied Surface Science</i> , 2008, 254, 5781-5790.	6.1	16

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55	Engineering the semiconductor/oxide interaction for stacking twin suppression in single crystalline epitaxial silicon(111)/insulator/Si(111) heterostructures. <i>New Journal of Physics</i> , 2008, 10, 113004.	2.9	24
56	Epitaxy of single crystalline PrO ₂ films on Si(111). <i>Applied Physics Letters</i> , 2008, 93, 032905.	3.3	25
57	The influence of lattice oxygen on the initial growth behavior of heteroepitaxial Ge layers on single crystalline PrO ₂ (111)•Si(111) support systems. <i>Journal of Applied Physics</i> , 2008, 103, 084110.	2.5	30
58	Lattice engineering of dielectric heterostructures on Si by isomorphic oxide-on-oxide epitaxy. <i>Journal of Applied Physics</i> , 2008, 103, 084102.	2.5	12
59	Self-assembled Ge nanocrystals on high-k cubic Pr ₂ O ₃ (111)•Si(111) support systems. <i>Journal of Applied Physics</i> , 2007, 102, 034107.	2.5	22
60	Structural and physical analysis on MOCVD Ti–Si–N films. <i>Journal of Physics and Chemistry of Solids</i> , 2007, 68, 1046-1051.	4.0	9
61	Combined IR and XPS analysis of the native (1 0 0) surface of single-crystalline silicon after HF _{aq} etching. <i>Surface and Interface Analysis</i> , 2007, 39, 836-844.	1.8	12
62	Characterization of ALD-deposited Al oxide films for high-k purposes: A chemical investigation. <i>Materials Science in Semiconductor Processing</i> , 2006, 9, 1000-1005.	4.0	0
63	Auger and XPS characterization of a multi layered Ti–Co–Si system for self aligned silicides purposes: a stoichiometry and chemical investigation. <i>Materials Science and Engineering B: Solid-State Materials for Advanced Technology</i> , 2004, 114-115, 203-208.	3.5	0
64	Detection of Metal Segregation at the Oxide-Silicon Interface. <i>Journal of the Electrochemical Society</i> , 2002, 149, G429.	2.9	13
65	Interface properties of annealed and nitrided HTO layers. <i>Microelectronic Engineering</i> , 2001, 59, 379-384.	2.4	2
66	Metal contamination reduction in the evolution of ion implantation technology. , 0, , .		4